

**METHOD FOR DETERMINING SEMICONDUCTOR OVERLAY ON
GROUNDRULE DEVICES**

ABSTRACT OF THE DISCLOSURE

5 A method of determining overlay error comprises creating a first and second
layers of an integrated circuit, each having an active circuit feature and an adjacent kerf
area. Each kerf area includes a first measurement feature separated from and
corresponding substantially to the layer's active circuit feature. The circuit and kerf areas
of the layers are substantially superimposed. The distance of separation between the
active circuit feature and the layer kerf measurement feature in each layer in the direction
10 of overlay error is the same. The second layer kerf measurement feature is displaced
from the first layer kerf measurement feature in a direction perpendicular to the direction
that the overlay error is to be determined. Overlay error is determined by measuring
distance of separation in the direction of overlay error between the common points of
reference of each of the first and second layer kerf measurement features.

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